

<b>Form 1449 (Modified)</b>  <b>Information Disclosure Statement By Applicant</b>  (Use Several Sheets if Necessary)	Atty Docket No.	Application No.:
	KLA1P119/P1158	10/760,149
	Applicant:	
	Mieher et al.	
	Filing Date:	01-17-2004
Group:	2877	
Confirmation No.:	7190	

### U.S. Patent Documents

Examiner Initial	No.	Patent No.	Date	Patentee	Class	Sub-class	Filing Date
	A						

### Foreign Patent or Published Foreign Patent Application

Examiner Initial	No.	Document No.	Publication Date	Country or Patent Office	Class	Sub-class	Translation	
							Yes	No
	B							

### Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	C1	Xinhui Niu, "Spectral Scatterometry for CD Control", <a href="http://buffy.eecs.berkeley.edu/IRO/Summary/98abstracts/xniu.2.html">http://buffy.eecs.berkeley.edu/IRO/Summary/98abstracts/xniu.2.html</a> Downloaded from the internet on May 14, 2002. 1 page.
	C2	Xinhui Niu, et al, "Specular Spectroscopic Scatterometry in DUV Lithography", Metrology, Inspection and Process Control for Microlithography XII SPIE's 24 <sup>th</sup> Annual International Symposium on Microlithography, SPIE February 1999. Proc. SPIE Int. Soc. Opt. Eng. 3677, 159 (1999). 10 pages.
	C3	Joseph C. Pellegrini, "Emerging Trends in Photolithography Analysis and Control", New Vision Systems, Inc., Cambridge, MA., presented at IEEE special invitation conference, 1996. 8 pages.
	C4	Michael Yeung, "Inverse Obstacle Problem in Ellipsometric Scatterometry", one-page summary printed in the Technical Program for PIERS 2002, presented at the Progress In Electromagnetics Research Symposium, Cambridge, MA., July 1, 2002. 1 page.
Examiner		Date Considered

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.